Range & Defects in Channeled 10 MeV Dopants in Si(100)

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- 1. A bit about stopping powers
- 2. Implant tool for channeled ions (S-UHE)
- 3. Implants and Range data
- 4. A bit about **photoluminescence**
- 5. Comparison of **PL recombination intensity** for **channeled** and "**random**" beam incidence.
- 6. Other recombination-sensitive probes: PMR ("TW")
- 6. PL recombination center "intermittencies"
- 7. Summary



Abstract

Low-dose **7.5 MeV B**⁺ and **10 MeV P**⁺ **and As**⁺ profiles in Si(100) with "**random**" (7/23 tilt/twist angles) and **highly-channeled** (0/0) ion beam-crystal orientations were studied with **SIMS**, the MC-code, **IMSIL**, and by photoluminescence (**PL**) and a variety of other carrier recombination sensitive defect metrologies (**JPV, PMR**).

Time signatures of curious "**intermittencies**" in the PL signals are also discussed.



A bit about Stopping Powers

Stopping powers of ions (eV/Å) in matter are a sum of 2 types of collisions:

$$S(eV/Å) = S_{el} + S_{nuc}$$

Electronic stopping: S_{el} (collisions of ions with loosely bound electrons) **Nuclear stopping:** S_{nuc} (collisions of ions with core electrons & nuclei)

Highly-channeled ion profiles are characterized by lower S_{nuc} values and deeper profiles.

Lower S_{nuc} values should create less damage (strong atom displacement collisions).





Electronic (S_{el}) and nuclear (S_{nuc}) stopping powers (eV/Angstrom) in Si for B, P and As from 1keV to 10 MeV.

Implant tool: SMIT S-UHE (Ultra-high Energy)



LINAC acceleration with 18 RF (13.46 Mz, 80 kV), sequential quadrupole focus elements, electrode phase & amplitude control for ion velocity filtering.

Magnetic ion energy filter, electrostatic scanner, parallelizing. Deflection energy filter before wafer.

Folded beamline: long-path beam alignment control.

lon energy range: 6.8 MeV (As, P), 5MeV (B).

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Single charge ions:
2 – 780 puA.
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Implants & Range

IMSIL: A MC code for IMplants in SILicon (100): Prof. Gerhard Hobler, TUWein



SIMS and IMSIL profiles for channeled (0/0) & random (7/23) incidence 7.5 MeV B and 10 MeV P and As implants at 25°C.



A bit about photoluminescence (PL)

Luminescence Timeline:

- 1. Electrons excited into conduction band by energy (electron or photon) >1.1 eV.
- Electrons rapidly loses energy to conduction ^E_g, band edge (by phonon emission).
- 3. Si band alignment requires coupling with phonons or mid-gap carrier recombination centers (damage) for electrons to return to valance band.
- All transitions can emit phonons (heat) or photons (PL and CL signal).

Radiative (light) transitions are a small fraction of total transitions: 1:1e-7.



Cathodo (electron driven) luminesce





Photoluminescence Signals: Annealed B



PL images, showing defect-assisted recombination light for wavelengths >1300 nm, for random and channeled 7.5 MeV B implants at a dose of 3e12 B/cm² (right) and annealing at 950° C for 3 minutes.

Note the dense radiative recombination centers in the random PL data for 7.5 MeV B compared to the relatively sparse radiative recombination centers (in circles) for the channeled orientation implant.



The image field of view is 175 x 140 um.

Radiative recombination at damage centers.

Generally λ > 1300 um. (photon <1.1 eV)

Number density of recombination events:

 N_{eh} (recombination) = S_{in} (hv>Eg) * (Absorption fraction) * [P_{eh} = [$N^{non-rad}$ + N^{rad}]] where: S_{in} (hv>E_{gap}) = excitation *input) signal power density with (hv>E_{gap}) Absorption fraction = power incident - power reflected P_{eh} = probability of e-h generation per absorbed hv =100% (?)

Normalized Defect Band PL Signal

 $[S^{PL}_{SRH}/S^{PL}_{BB}] = [NDPL] \approx n_{SRH}$

(Otherwise, $n_{SRH} = \sum [cluster brightness_j * cluster size_j * # clusters(j)]$ with apologies to M. Planck, A. Einstein, etc.



Defect Band PL: annealed samples

Defect band PL, at wavelengths >1300 um, show strong effects of channeling (lower defect levels), especially for the high S_{nuc} ions, As and P.

B implanted samples have low defect signals (low S_{nuc}), with channeling effects in the noise.





Photo-modulated Reflectance: PMR



Photo-modulated reflectance (PMR) signals are strongly sensitive to shallow damage (As & P) and less sensitive to deeper B damage. Clear channeling effects on carrier recombination at defects are seen for As and P implants.



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PL "Blinking" during Recombination



Individual PL defect signals over a time sample of ≈40 min, showing 3 levels of luminosity, indicating a change of state at a defect site as carriers are recombined. A PL "intermittency".



Jahn-Teller* Distortion (1937).

"any non-linear molecular system in a degenerate electronic state will be unstable and will undergo distortion to form a system of lower symmetry and lower energy, thereby removing the degeneracy."



Postulate: Vibrations and structure of defect (including metal precipitates) sites may change with phonon emission during carrier recombination. A topic worthy of study and <u>PL intermittencies</u> may be possible <u>defect spectroscopy</u>.



Edward Teller* (1908-2003): Hydrogen bombs, Star Wars, etc.

Summary

- 1. Carrier (electrons & holes) recombination occurs by:
 - (1) phonon-assisted (temperature dependent) band-to-band transition or
 - (2) coupling with damage/defect sites (in mid-gap regions). More phonons.
- 2. Carrier recombination results in measurable effects:
 - (1) <u>charge loss</u>:[Junction photovoltage(JPV):R_{sheet}, Junction leakage current]
 - (2) phonon emission (heating): [Photo-modulated Reflection (PMR), aka "TW"]
 - (3) photon emission (IR light): [Photo/Cathodo-Luminescense (PL/CL)].
- 3. Photoluminescence (PL) provides quantifiable measures of defect densities throughout the full volume of a doped junction & depletion layer.
 - (1) Radiative center density (at low damage density levels)
 - (2) Mid-gap transition intensity (at high & low damage levels)
- 4. Work to be done: (1) calibration of PL intensity levels with IC leakage,
 - (2) correlation with other recombination-sensitive measures (PMR, JPV, etc.),
 - (3) <u>understanding</u> of <u>PL intensity fluctuation</u> & <u>defect center structure</u>.



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Good Fortune in 2023, the Year of the Rabbit.



Nengajo for 2023, Year of the Rabbit with sketch of Rakoto Honen-in south gate.

